

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 7,103,972 B2
APPLICATION NO. : 10/695147
DATED : September 12, 2006
INVENTOR(S) : Chien-Hua Chen et al.

Page 1 of 1

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

On the face page, in field (75), in "Inventors", in column 1, line 1, delete "C rvallis" and insert -- Corvallis --, therefor.

On the face page, in field (57), under "Abstract", in column 2, lines 1-3, delete "A fluid ejection device comprising a composite substrate, wherein the composite substrate has two substrates with a patterned etch mask therebetween, and a fluid channel." and insert -- A Method of fabricating a fluid ejection device comprising: bonding a top surface of a first substrate to a bottom surface of a second substrate, wherein a patterned etch mask layer is formed on at least one of the top surface of the first substrate and the bottom surface of the second substrate; and etching a fluid channel in the first and second substrates extending through an opening in the patterned etch mask layer. --, therefor.

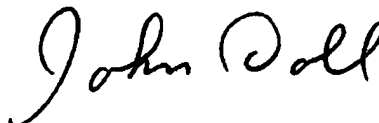
In column 2, line 53, delete "second" and insert -- first --, therefor.

In column 2, line 54, delete "forming" and insert -- form --, therefor.

In column 6, line 36, in Claim 9, before "surface" delete "to" and insert -- top --, therefor.

Signed and Sealed this

Fourteenth Day of April, 2009



JOHN DOLL
Acting Director of the United States Patent and Trademark Office